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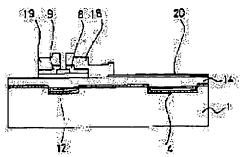
HIROSE GIICHI

(54) LIQUID CRYSTAL DISPLAY DEVICE AND ITS PRODUCTION

(57)Abstract:

PURPOSE: To absorb the thickness of a gate line formed by plating by a trench provided in a glass substrate and to drastically decrease the line resistance of the gate line by embedding the gate line into the trench.

CONSTITUTION: The trench 4 is provided in the glass substrate 1 and the gate line 12 formed by the nonelectric field and electric field plating is embedded into this trench 4. Then, the level difference of the gate line 12 can be absorbed by the recess of the trench 4 even if the gate line is formed thick. As a result, the thick formation of the gate line 12 is possible and its sectional area can be increased and, therefore, the resistance of the gate line 12 is easily decreased. The line resistance can be lowered even in spite of use of metals, such as Cr and Ni, which are high in specific resistance but are inexpensive as the material for the gate line 12. The resist layer for forming the trench 4 is used as a common mask up to the non-electric field and electric



field plating of the gate line 12 and, therefore, the production by simple self-alignment is possible.

LEGAL STATUS

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